

United States Patent and Trademark Office

w

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/761,784	01/21/2004	Wei Pan	SLA0861 (SLA0603D)	3531	
7590 04/15/2005			EXAMINER		
David C. Ripma, Patent Counsel			COLEMAN, WILLIAM D		
Sharp Laboratories of America, Inc. 5750 N.W. Pacific Rim Boulevard			ART UNIT	PAPER NUMBER	
Camas, WA 9	8607		2823	2823	
			DATE MAILED: 04/15/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

-	Application No.	Applicant(s)
	10/761,784	PAN ET AL.
Office Action Summary	Examiner	Art Unit
	W. David Coleman	2823
The MAILING DATE of this communication a Period for Reply	appears on the cover sheet with the c	orrespondence address
A SHORTENED STATUTORY PERIOD FOR REF THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, and - If NO period for reply is specified above, the maximum statutory perion. - Failure to reply within the set or extended period for reply will, by state any reply received by the Office later than three months after the may be a searned patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a reply be tin reply within the statutory minimum of thirty (30) day iod will apply and will expire StX (6) MONTHS from tute, cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).
Status		
1) Responsive to communication(s) filed on 21	January 2004.	
2a) ☐ This action is FINAL . 2b) ☑ T		
3) Since this application is in condition for allow closed in accordance with the practice under	wance except for formal matters, pro	
Disposition of Claims		
4) ☐ Claim(s) 19-21 is/are pending in the applica 4a) Of the above claim(s) is/are without 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 19-21 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and	Irawn from consideration.	
Application Papers		
9) The specification is objected to by the Exam 10) The drawing(s) filed on is/are: a) a Applicant may not request that any objection to t Replacement drawing sheet(s) including the corr 11) The oath or declaration is objected to by the	accepted or b) objected to by the label of the drawing(s) be held in abeyance. Secrection is required if the drawing(s) is objected to by the label of the drawing(s) is objected to be accepted to by the label of the accepted to be accepted to accepted to be accepted to a	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for fore a) All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the papplication from the International Bur * See the attached detailed Office action for a	ents have been received. ents have been received in Applicati priority documents have been receive eau (PCT Rule 17.2(a)).	ion No ed in this National Stage
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail D 708) 5) Notice of Informal F 6) Other:	

Application/Control Number: 10/761,784 Page 2

Art Unit: 2823

DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 19, 20 and 21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Omura, U.S. Patent 6,028,362.

Omura discloses a semiconductor device substantially as claimed. Please see FIGS. 1-42 where Omura teaches the following limitations.

Pertaining to claim 19, <u>Omura</u> teaches an integrated circuit having a copper interconnect there formed over a layer of barrier metal comprising:

a substrate 40, including active regions S/D, vias and trenches (not numbered) for interconnect structures;

a metal barrier layer 50 formed on the substrate, wherein said metal barrier layer is taken from the group of materials consisting of Ta, TiN, TaN and TiSiN, and formed to a thickness of between about 5 nm to 10 nm (see column 9, lines 1-6);

an ultra thin film layer of tungsten 52 formed on the barrier metal layer 50; and a copper thin film 44 layer formed on the tungsten ultra thin film layer to a thickness to sufficient to fill the vias and trenches in the structure.

However, Omura fails to teach wherein the thickness of the tungsten formed on the barrier metal layer is about 1 nm to 5nm. Given the teaching of the references, it would have

been obvious to determine the optimum thickness, temperature as well as condition of delivery of the layers involved. See *In re Aller, Lacey and Hall* (10 USPQ 233-237) "It is not inventive to discover optimum or workable ranges by routine experimentation. Note that the specification contains no disclosure of either the critical nature of the claimed ranges or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen dimensions or upon another variable recited in a claim, the Applicant must show that the chosen dimensions are critical. *In re Woodruff*, 919 f.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

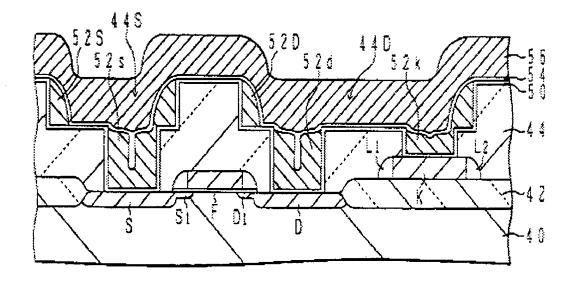
Any differences in the claimed invention and the prior art may be expected to result in some differences in properties. The issue is whether the properties differ to such an extent that the difference is really unexpected. *In re Merck & Co.*, 800 F.2d 1091, 231 USPQ 375 (Fed. Cir. 1986)

Appellants have the burden of explaining the data in any declaration they proffer as evidence of non-obviousness. *Ex parte Ishizaka*, 24 USPQ2d 1621, 1624 (Bd. Pat. App. & Inter. 1992).

An Affidavit or declaration under 37 CFR 1.132 must compare the claimed subject matter with the closest prior art to be effective to rebut a prima facie case of obviousness. *In re Burckel*, 592 F.2d 1175, 201 USPQ 67 (CCPA 1979).

Application/Control Number: 10/761,784

Art Unit: 2823



- 3. Pertaining to claim 20, Omura teaches the integrated circuit of claim 19 wherein said ultra thin film layer of tungsten is formed from a precursor taken from the group of precursors consisting of WF₆ and W(CO)₆.
- 4. Pertaining to claim 21, <u>Omura</u> teaches the method wherein said depositing a copper thin film includes depositing a layer of copper. However, <u>Omura</u> fails to teach the claimed thickness of the copper having a thickness of about 10 nm to 20 nm. The motivation of this rejection is of the same grounds as the rejection of claim 19 above.

Conclusion

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to W. David Coleman whose telephone number is 571-272-1856.

The examiner can normally be reached on Monday-Friday 9:00 AM - 5:30 PM.

Application/Control Number: 10/761,784

Art Unit: 2823

6. If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Olik Chaudhuri can be reached on 571-272-1855. The fax phone number for the

organization where this application or proceeding is assigned is 703-872-9306.

7. Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

W. David Coleman Primary Examiner

Page 5

Art Unit 2823

WDC